



(19)

(11) Publication number:

11

Generated Document.

PATENT ABSTRACTS OF JAPAN(21) Application number: **09246709**(51) Intl. Cl.: **B24B 37/00**(22) Application date: **11.09.97**

(30) Priority: (43) Date of application publication: 06.04.99 (84) Designated contracting states:	(71) Applicant: TEIJIN LTD (72) Inventor: ENOMORI MASATSUGU NISHIHARA TOSHIO ARAKI TADAAKI (74) Representative:
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(54) POLISHING PAD

(57) Abstract:

PROBLEM TO BE SOLVED: To resolve clogging with simple dressing only by setting the hardness of the surface of a polishing pad to a specific value.

SOLUTION: A nonwoven fabric forming a polishing pad is not limited in particular as long as it is made of fibers, and the hardness (JIS K6301 A type) of the surface of the obtained polishing pad is set to 85°-99°, preferably 88°-98°, to increase the flatness required for a CMP polishing pad. The nonwoven fabric is made of thermal fusion fibers and thermal nonfusion fibers. The ratio between the thermal fusion fibers and the thermal nonfusion fibers is preferably set to 10-50 wt.%: 50-90 wt.%. When the ratio of the thermal fusion fibers is below 10 wt.%, the hardness of the obtained polishing pad becomes insufficient after a heat treatment is applied later. When the ratio of the thermal fusion fibers is larger than 50

Nonwoven fabric

wt.%, fusion proceeds too much at the time of the heat treatment, and the permeability of a polishing slurry is deteriorated.

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